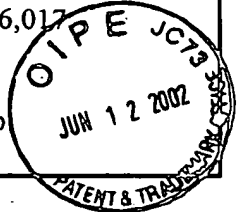


Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	NOVLP030/NVLS-000497	10/016,017
	Applicant:	
	Gopinath et al.	
Filing Date	Group	
December 12, 2001	2813	



U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

RECEIVED
 JUN 17 2002
 NC 2800 MAIL ROOM

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
<i>JS</i>	A	Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Appl. No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.
Examiner	Date Considered	
<i>hanna Schults</i>	<i>8/4/04</i>	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.